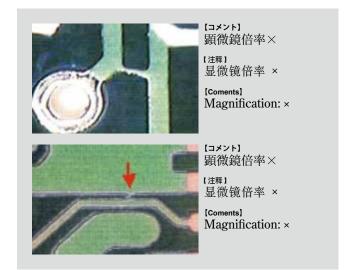
【原因・判断ポイント・発生工程】ネガタイプAWFの不透明部に付いた傷部が露光して出来たもの(AWF作製後~ET工程)

【原因、判断要点、发生工序】对 AWF 不透明区有 伤痕部位曝光时所引起的(AWF 制作后~ET 工序)。

## [Causes/processes involved/keys to judgment]

Exposure is made with a phototool with a scratch on the opaque area of the negative pattern causing the defect. (Preparation of phototool - etching process)



## 1-8-3-6 繊維状異物介在露光被り短絡/纤维杂物妨碍曝光的短路/ Short by photographic fogging by an adhered fibrous object

【特徴】複数の回路線にまたがって、比較的長く短絡している状態の欠陥、めっき面の凹凸は認められない

【特征】跨过多条线路比较长的短路缺陷,而不是镀层面的凹凸。

**[Characteristics]** A short of a relatively long distance extending several conductors. Unevenness of the plated surface is not observed.

【原因・判断ポイント・発生工程】DFRとAWF間に介在した繊維状異物により、AWFが浮き上がり状態となり、露光被りして出来たもの(露光工程~ET工程)

【原因、判断要点、发生工序】DFR 和 AWF 之间夹杂纤维杂物,AWF 鼓起而妨碍曝光所引起的(曝光工序~ET 工序)。

## [Causes/processes involved/keys to judgment]

Photographic fogging caused by lift of a phototool by a fibrous foreign object between dry film and a phototool generates the defect. (Exposure – etching process)

